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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/680,960	10/07/2003	Howard Ge	34261-8500	6075

21611 7590 06/20/2006

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EXAMINER

CHACKO DAVIS, DABORAH

ART UNIT	PAPER NUMBER
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1756

DATE MAILED: 06/20/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No.	Applicant(s)	
	10/680,960	GE ET AL.	
	Examiner	Art Unit	
	Daborah Chacko-Davis	1756	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE _____ MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 07 October 2003.
- 2a) ☐ This action is FINAL. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-18 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 1-18 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on _____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☐ All b) ☐ Some * c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. _____.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- | | |
|---|---|
| 1) <input checked="" type="checkbox"/> Notice of References Cited (PTO-892) | 4) <input type="checkbox"/> Interview Summary (PTO-413)
Paper No(s)/Mail Date. _____ |
| 2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948) | 5) <input type="checkbox"/> Notice of Informal Patent Application (PTO-152) |
| 3) <input checked="" type="checkbox"/> Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date <u>03/05, 07/05</u> . | 6) <input type="checkbox"/> Other: _____ |

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.

2. Claims 1-3, 5-7, 9-10, are rejected under 35 U.S.C. 102(a) as being anticipated by U. S. Patent Application Publication No. 2002/0182547 (Raguin).

Raguin, in the abstract, in [0007], [0008], [0009], [0010], [0035], [0039], [0040], [0041], [0052], [0053], discloses rotating a substrate and spray coating at an angle to the surface of the substrate (see figure 6E) a positive-tone or a negative-tone photoresist solution the surface of the substrate (to obtain deep etched structures at least 15 μ , or greater than 50 μ), and moving the spray nozzle across the substrate surface (diameter) at varying rates so as to ensure a thick photoresist film spread across the substrate surface uniformly (claims 1, 5, 9-10). Raguin, in [0033], discloses that the substrate is cleaned (primed) with suitable solvents, acid solutions (contact angle less than 90°) etc., prior to the spray coating of the photoresist solution (claims 2, and 6). Raguin, in [0035], discloses that the photoresist is spray coated in an environment that is saturated with vapor (humidity at least as high as 60%) (claims 3, and 7).

Claim Rejections - 35 USC § 103

3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

4. Claims 11, 13-18, are rejected under 35 U.S.C. 103(a) as being unpatentable over U. S. Patent Application Publication No. 2002/0182547 (Raguin) in view of Research Disclosure (Kenneth Mason Publications, vol.324, April 1991, hereinafter referred to as RD91).

Raguin, in the abstract, in [0007], [0008], [0009], [0010], [0035], [0039], [0040], [0041], [0052], [0053], discloses rotating a substrate and spray coating at an angle to the surface of the substrate (see figure 6E) a positive-tone or a negative-tone photoresist solution the surface of the substrate (to obtain deep etched structures at least 15 μ , or greater than 50 μ), and moving the spray nozzle across the substrate surface (diameter) at varying rates so as to ensure a thick photoresist film spread across the substrate surface uniformly. Raguin, in [0033], discloses that the substrate is dried and cleaned (primed) with suitable solutions, solvents, acid solutions (contact angle less than 90°) etc., followed by thorough drying prior to the spray coating of the photoresist solution (claims 11, 13-15, and 17-18). Raguin, in [0035], discloses that the photoresist is spray coated in an environment that is saturated with vapor (humidity at least as high as 60%) (claim 16).

The difference between the claims and Raguin is that Raguin does not disclose immersing the substrate in a solution, followed by rinsing in ultra pure wafer.

RD91, in the disclosure, teaches immersing (washing in a solution) followed by thorough rinsing in wafer prior to priming (cleaning in acid) prior to resist lamination.

Therefore, it would be obvious to a skilled artisan to modify Raguin by employing the washing and water rinsing processes suggested by RD91 because RD91, discloses that doing so will prevent insufficient adhesion between the substrate and the photoresist layer to be laminated, and Raguin, in [0033], suggests thorough cleaning of the substrate so as to promote adhesion of the photosensitive material.

5. Claims 4, 8, are rejected under 35 U.S.C. 103(a) as being unpatentable over U. S. Patent Application Publication No. 2002/0182547 (Raguin) in view of U. S. Patent Application Publication No. 2004/01853568 (Dammel et al., hereinafter referred to as Dammel).

Raguin is discussed in paragraph no. 2.

The difference between the claims and Raguin is that Raguin does not disclose that the photoresist is a cyclohexanone-based resist (claim 4) and that the photoresist is a propylene glycol monomethyl ether acetate based resist (claim 8) and that the solvent is methyl-ethyl-ketone.

Dammel, in [0034], discloses that the resist can be a propylene glycol monomethyl acetate based resist or a cyclohexanone based resists and that the solvent employed in the composition is ketone based solvent.

Therefore, it would be obvious to a skilled artisan to modify Raguin by employing the resist compositions suggested by Dammel because Raguin, in [0010], discloses using photoresist material composition to form a layer of thickness greater than 50 μ , and Dammel, in [0028], [0035], and [0036], discloses priming the substrate prior to spray coating the substrate with the claimed composition in order to promote adhesion of the thick photoresist layer with the surface of the substrate.

6. Claim 12 is rejected under 35 U.S.C. 103(a) as being unpatentable over U. S. Patent Application Publication No. 2002/0182547 (Raguin) in view of Research Disclosure (Kenneth Mason Publications, vol.324, April 1991, hereinafter referred to as RD91) as applied to claims 11, 13-18 above, and further in view of U. S. Patent No. 4,791,465 (Sakai et al., hereinafter referred to as Sakai).

Raguin in view of RD91 is discussed in paragraph no. 4.

The difference between the claims and Raguin in view of RD91 is that Raguin in view of RD91 does not disclose immersing the substrate in a peroxide-sulfuric solution for five to fifteen minutes and rinsing in ultra pure water for five to ten minutes (claim 12).

Sakai, in col 4, lines 39-56, discloses that the substrates are immersed in peroxide+sulfuric acid solution followed by a water rinsing process for several minutes.

Therefore, it would be obvious to a skilled artisan to modify Raguin in view of RD91 by employing the solution mixtures suggested by Sakai because Raguin, in [0033], discloses that solvents or solutions or acid solutions can be employed for

cleaning the substrate surface in order to promote adhesion of the surface with the photosensitive material and reduce the probability of defects caused by surface contamination.

Conclusion

7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Daborah Chacko-Davis whose telephone number is (571) 272-1380. The examiner can normally be reached on M-F 9:30 - 6:00. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark F Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is (571) 273-8300. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

dcd

June 14, 2006.


JOHN A. MCPHERSON
PRIMARY EXAMINER